

**US DEPARTMENT OF COMMERCE
PATENT AND TRADEMARK OFFICE**

APPLICANT: MARTIN RICHARDSON

FOR: EUV, XUV, AND X-RAY WAVELENGTH SOURCES CREATED FROM LASER PLASMA
PRODUCED FROM LIQUID METAL SOLUTIONS, AND NANO-SIZE PARTICLES IN SOLUTIONS

LIST OF ART CITED BY APPLICANTU.S. PATENT DOCUMENTS

EXAMINER	DOCUMENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE	
CT ↓	AA	4,024,400	05/17/77	Blytas et al.	250	432	05/13/76
	AB	4,328,464	05/04/82	Pivirotto	330	4.3	02/07/80
	AC	4,700,371	10/13/87	Forsyth et al.	378	34	11/08/84
	AD	4,723,262	02/02/88	Noda et al.	378	119	12/26/85
	AE	4,866,517	09/12/89	Mochizuke et al.	378	119	09/10/87
	AF	4,953,191	08/28/90	Smither et al.	378	143	07/24/89
	AG	5,052,034	09/24/91	Schuster	378	121	10/29/90
	AH	5,126,755	06/30/92	Sharpe et al.	346	75	03/26/91
	AI	5,142,297	08/25/92	Eijkman et al.	346	1.1	03/26/90
	AJ	5,148,462	09/15/92	Spitsyn et al.	378	143	04/08/91
	AK	5,151,928	09/29/92	Hirose	378	119	08/20/91
	AL	5,243,638	09/07/93	Wang et al.	378	119	03/10/92
	AM	5,257,303	10/26/93	Das Gupta	378	85	08/03/92
	AN	5,317,574	05/31/94	Wang	372	5	12/31/92
	AO	5,459,771	10/17/95	Richardson et al.	378	119	04/01/94
	AP	5,577,091	11/19/96	Richardson et al.	378	119	01/13/95
	AQ	5,577,092	11/19/96	Kublak et al.	378	119	11/19/96
	AR	5,991,360	11/23/99	Matsui et al.	378	119	02/03/98
	AS	6,002,744	12/14/99	Hertz et al.	378	119	10/21/98
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AW	6,244,717	06/12/01	Dinger	359	859	05/28/99	

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FOREIGN PATENT DOCUMENTS

FA	JA57/41167	March 1982	JAPAN
FB	JA0267895	11/90	Iwamatsu

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Courtney Thomas 01.02.03